

Applicant(s): Michael E. Fossey et al.

WAFER INSPECTION SYSTEM FOR DISTINGUISHING PITS
AND PARTICLES

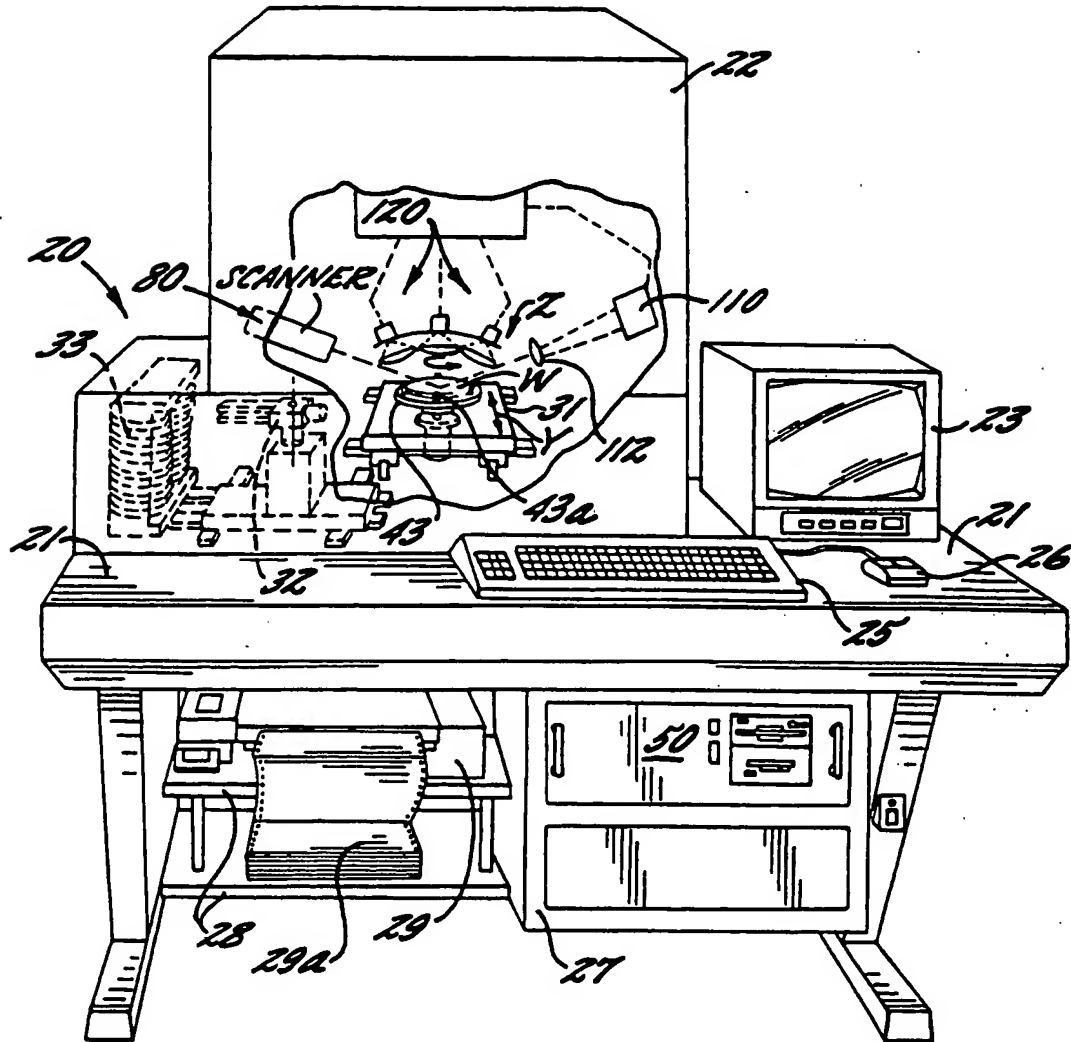


FIG. 1

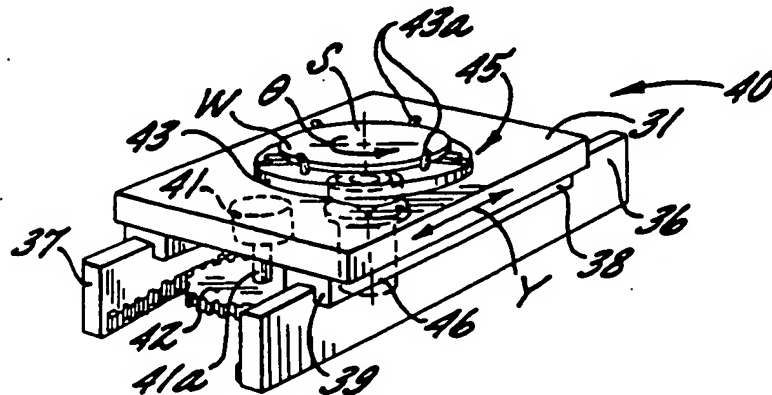


FIG. 2

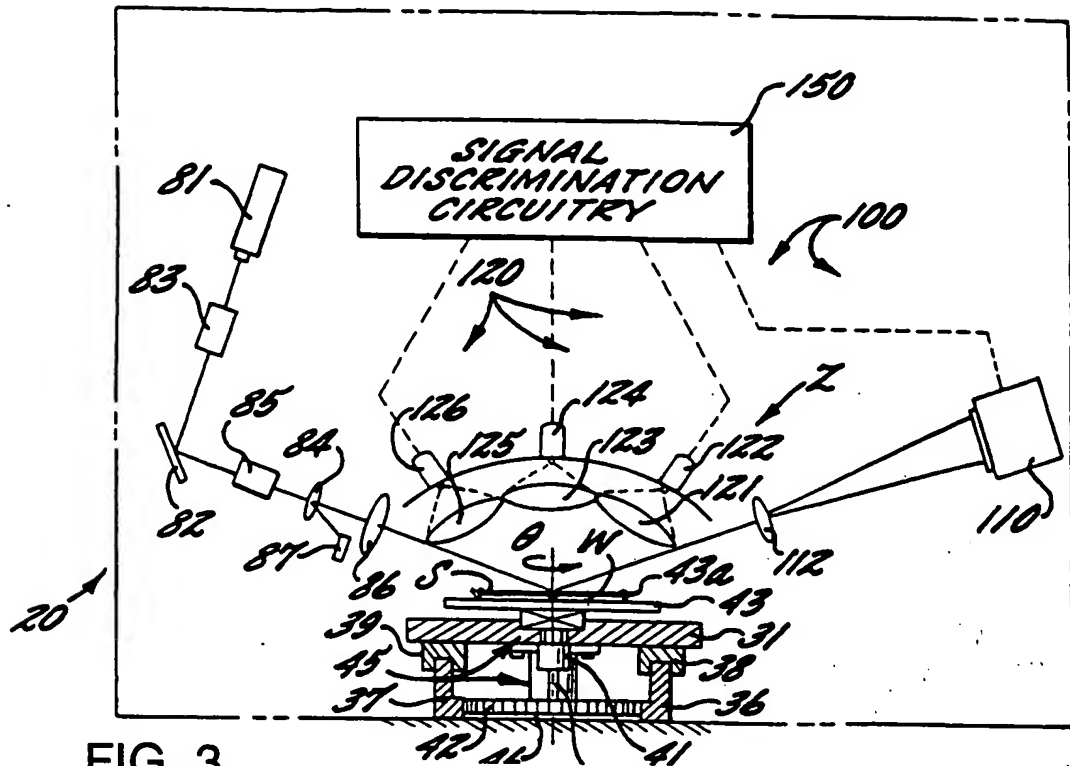


FIG. 3

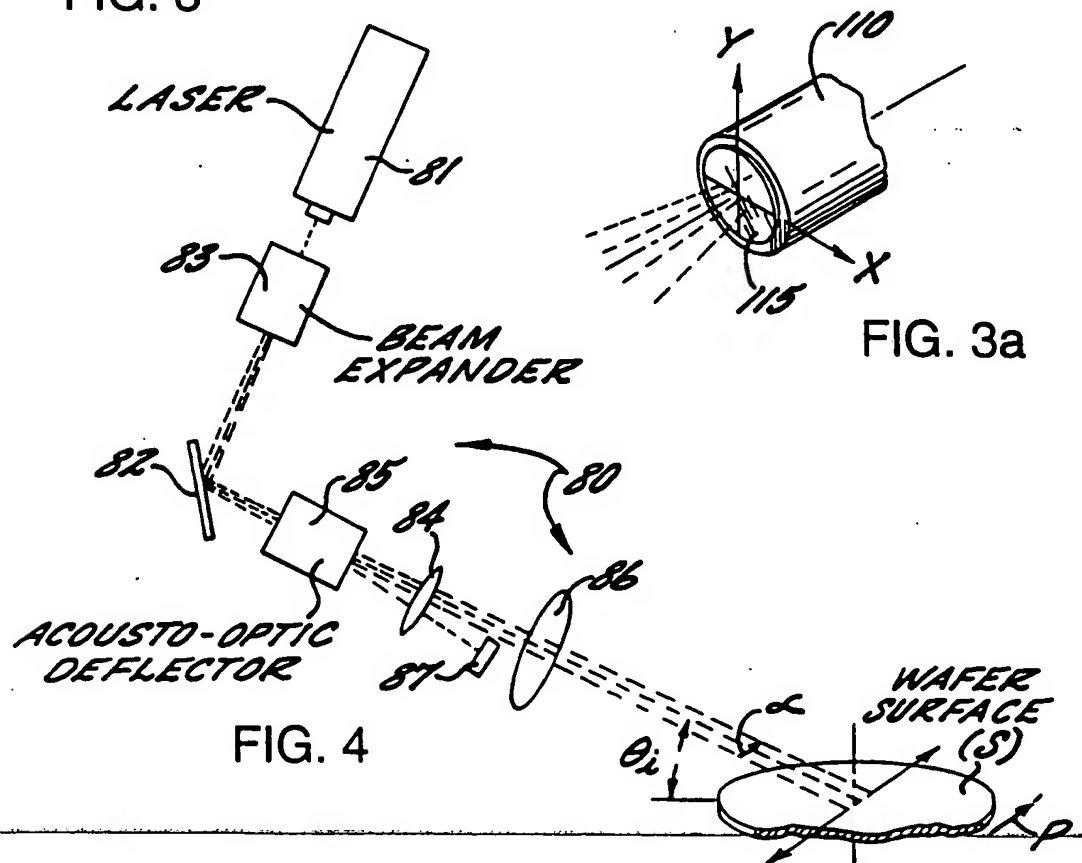


FIG. 4

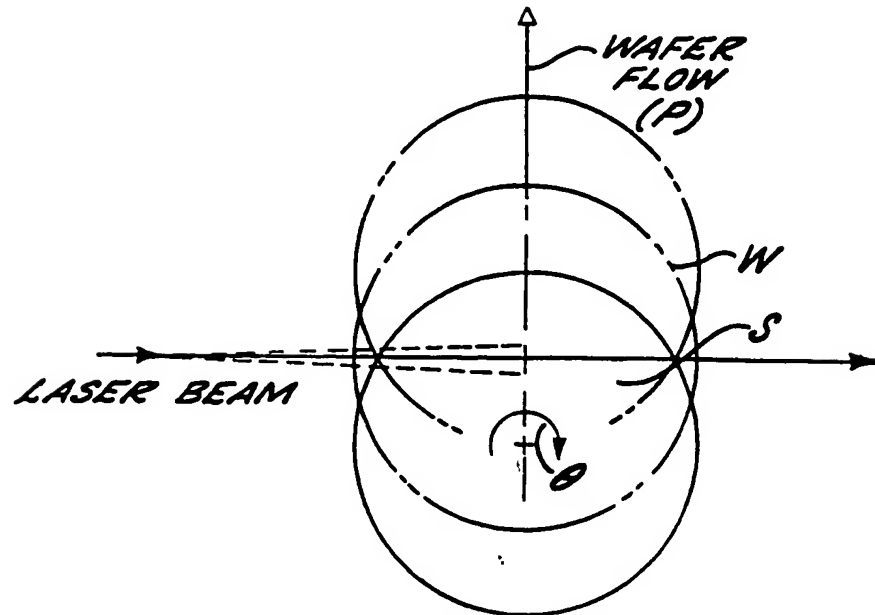


FIG. 5

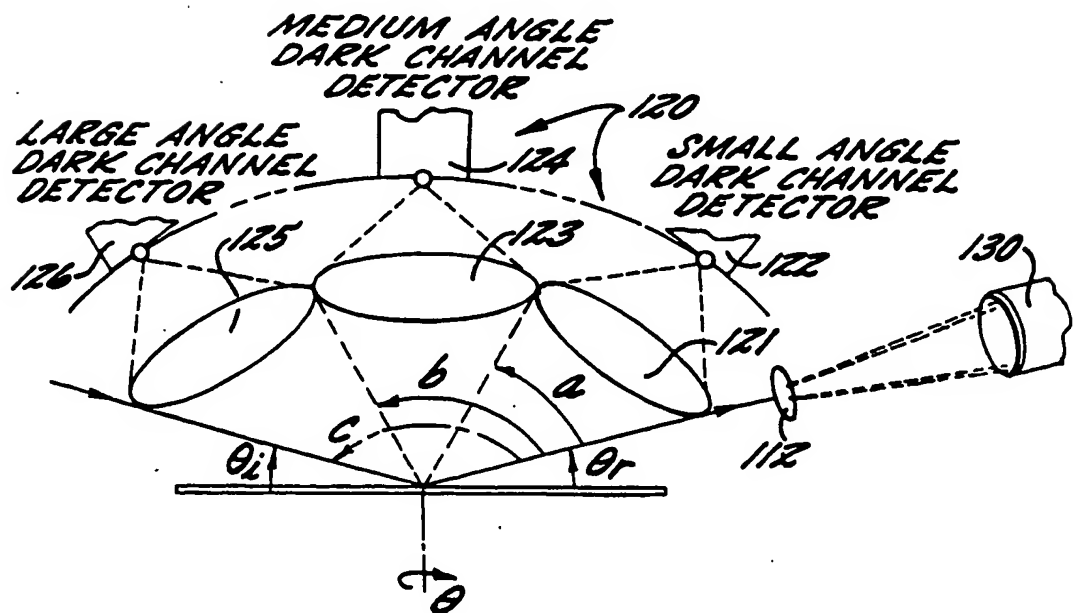


FIG. 6

Applicant(s): Michael E. Fossey et al.

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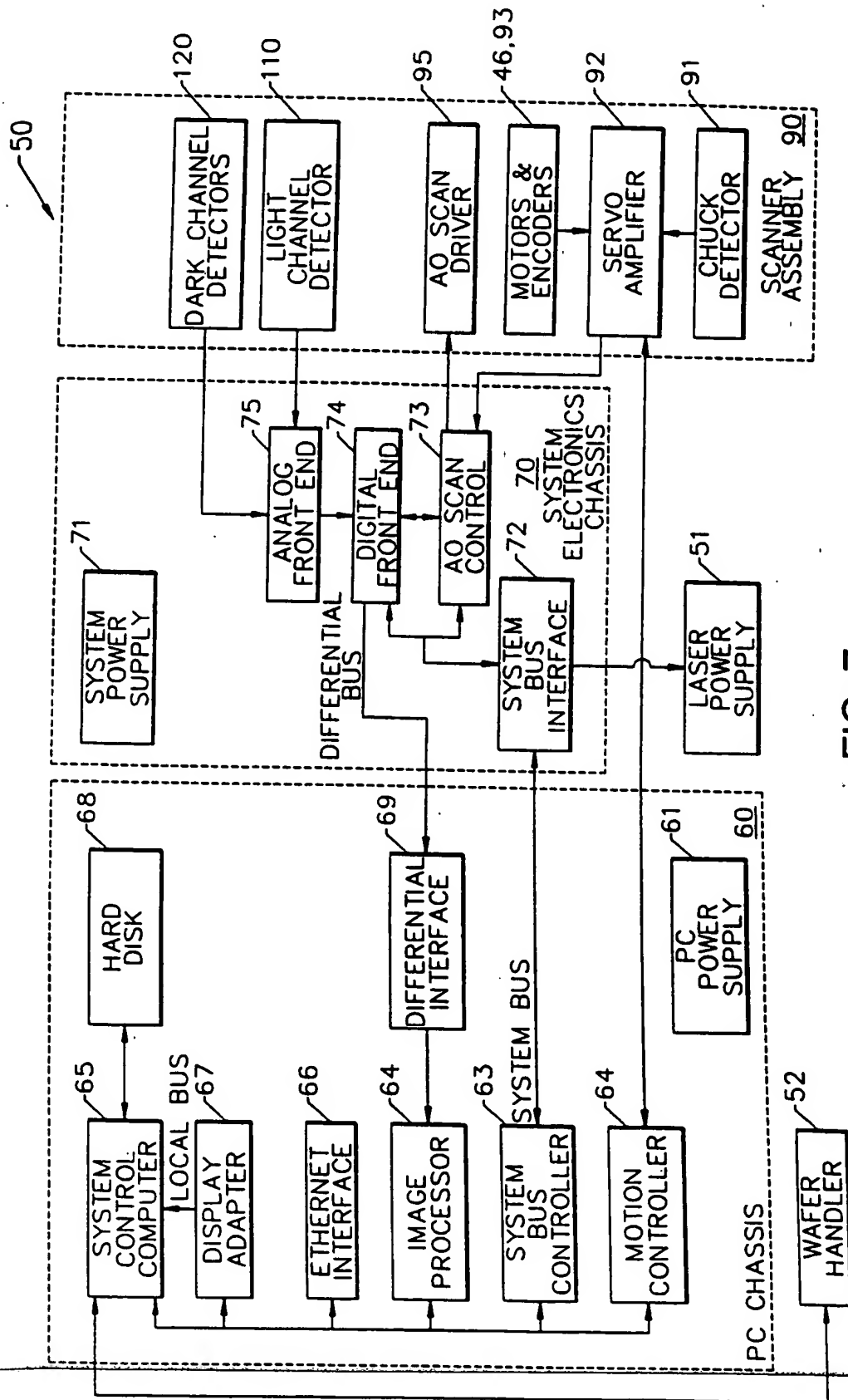


FIG. 7

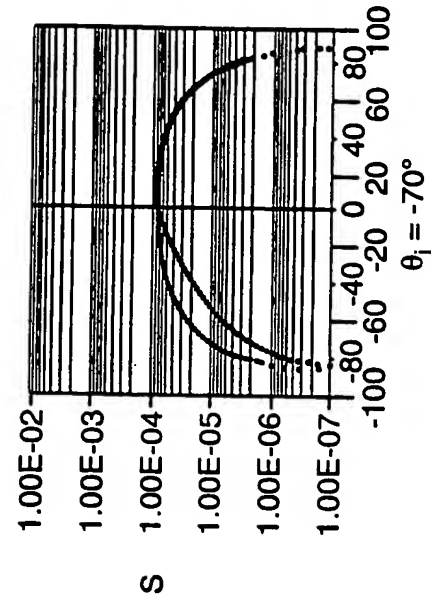


FIG. 8B

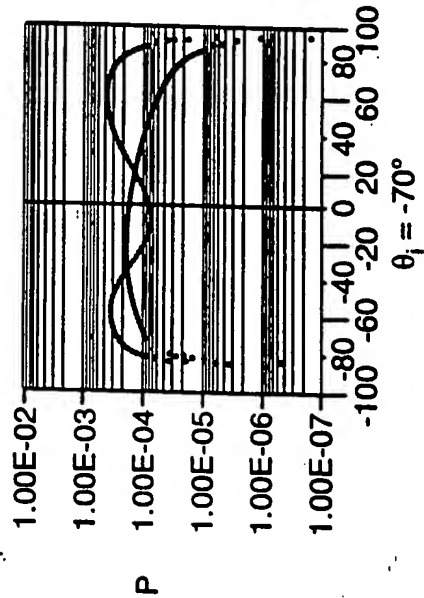


FIG. 8D

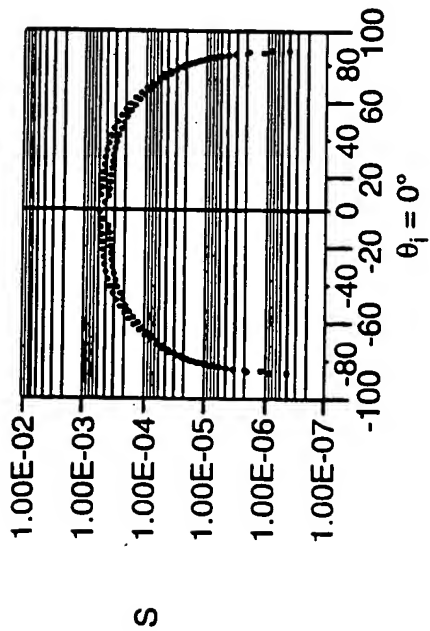


FIG. 8A

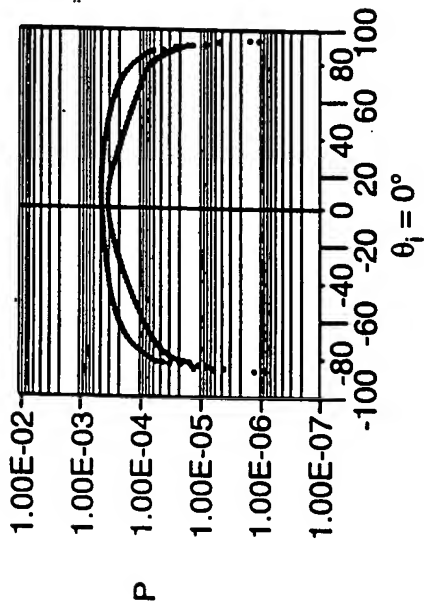


FIG. 8C

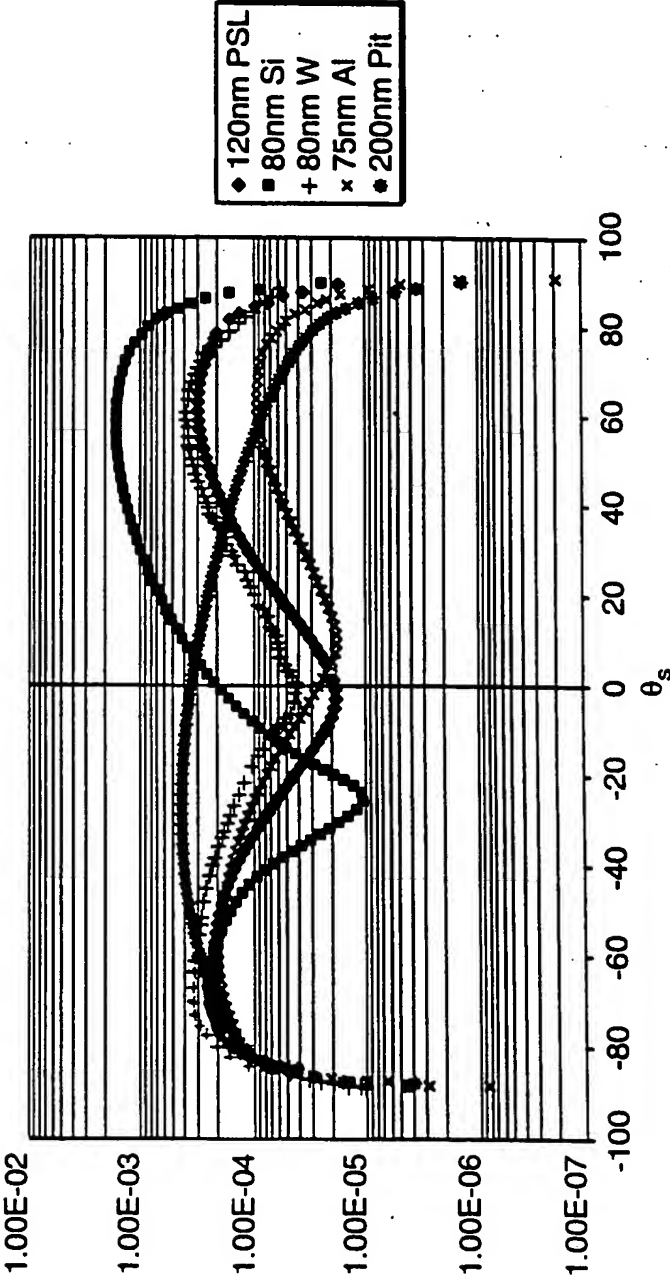


FIG. 9

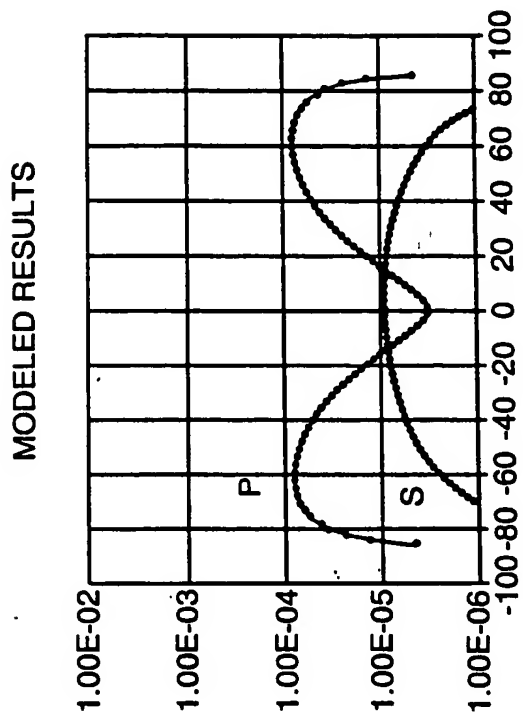


FIG. 10B

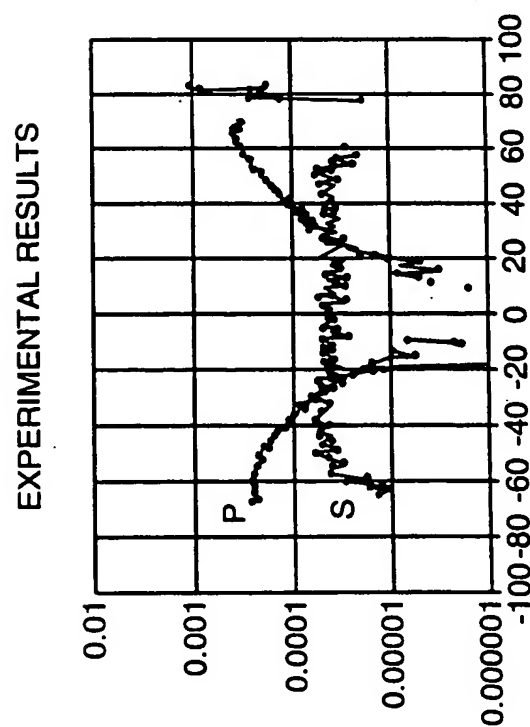


FIG. 10A

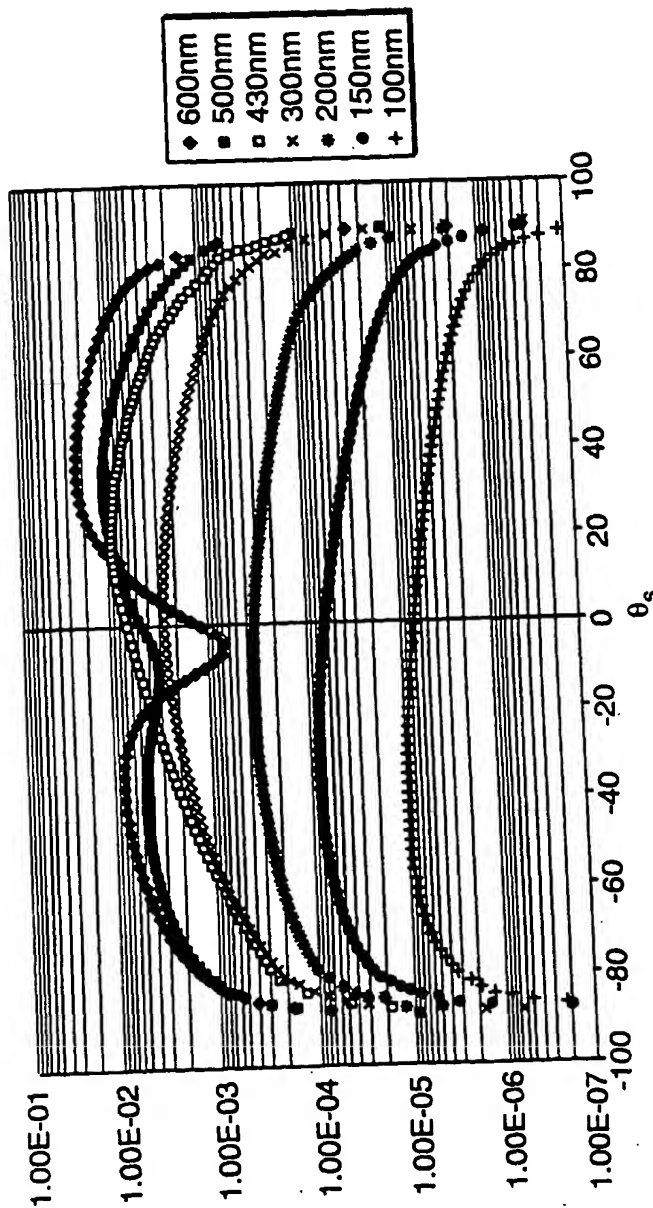


FIG. 11

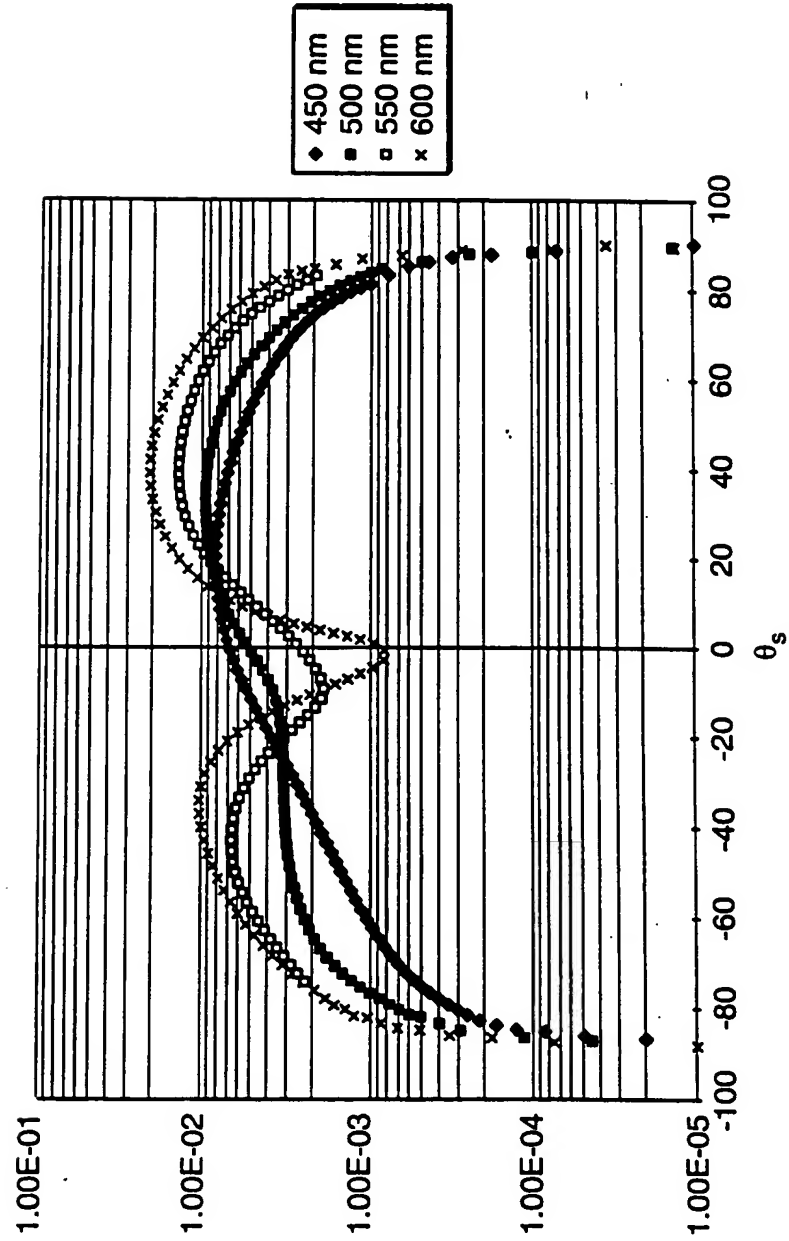


FIG. 12

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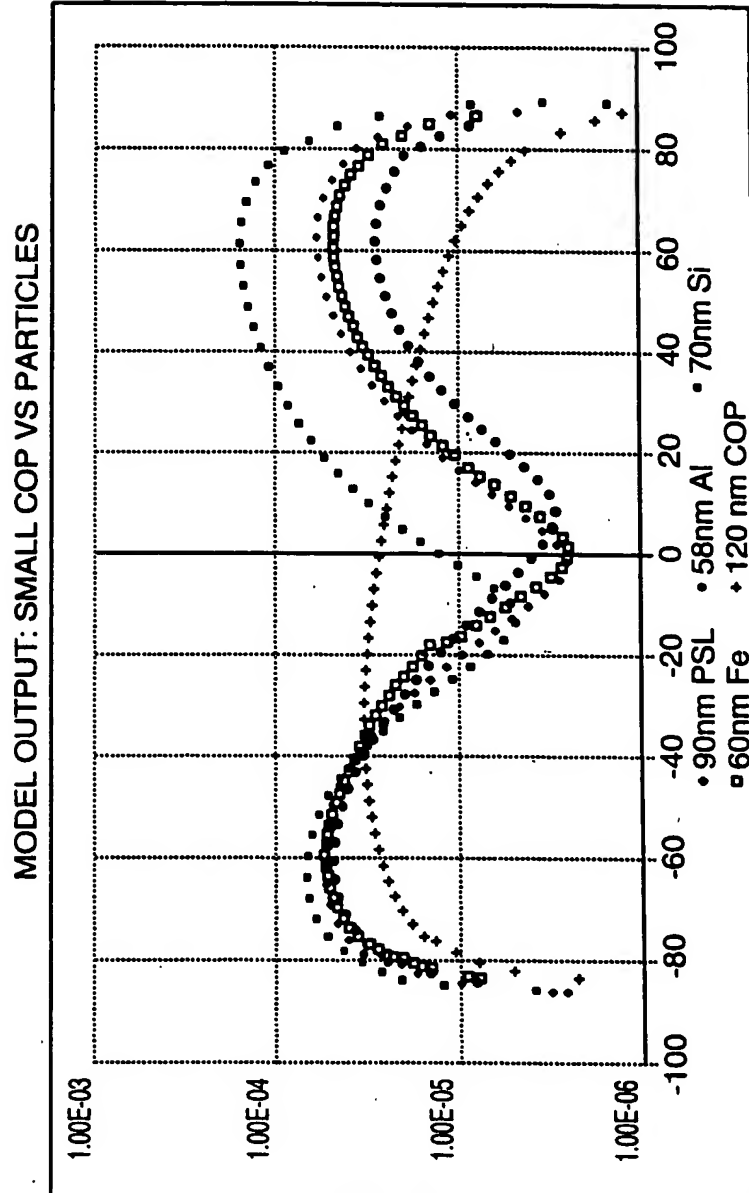
WAFER INSPECTION SYSTEM FOR DISTINGUISHING PITS
AND PARTICLES

FIG. 13

Applicant(s): Michael E. Fossey et al.

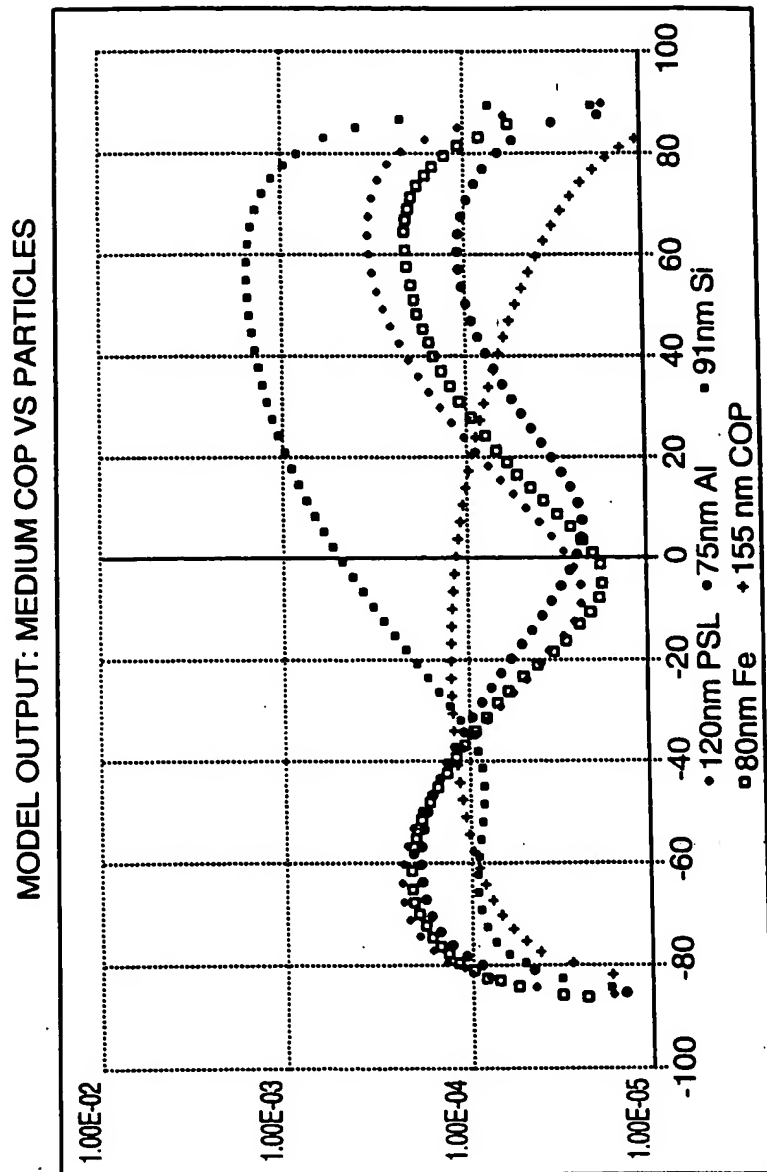
WAFER INSPECTION SYSTEM FOR DISTINGUISHING PITS
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FIG. 14

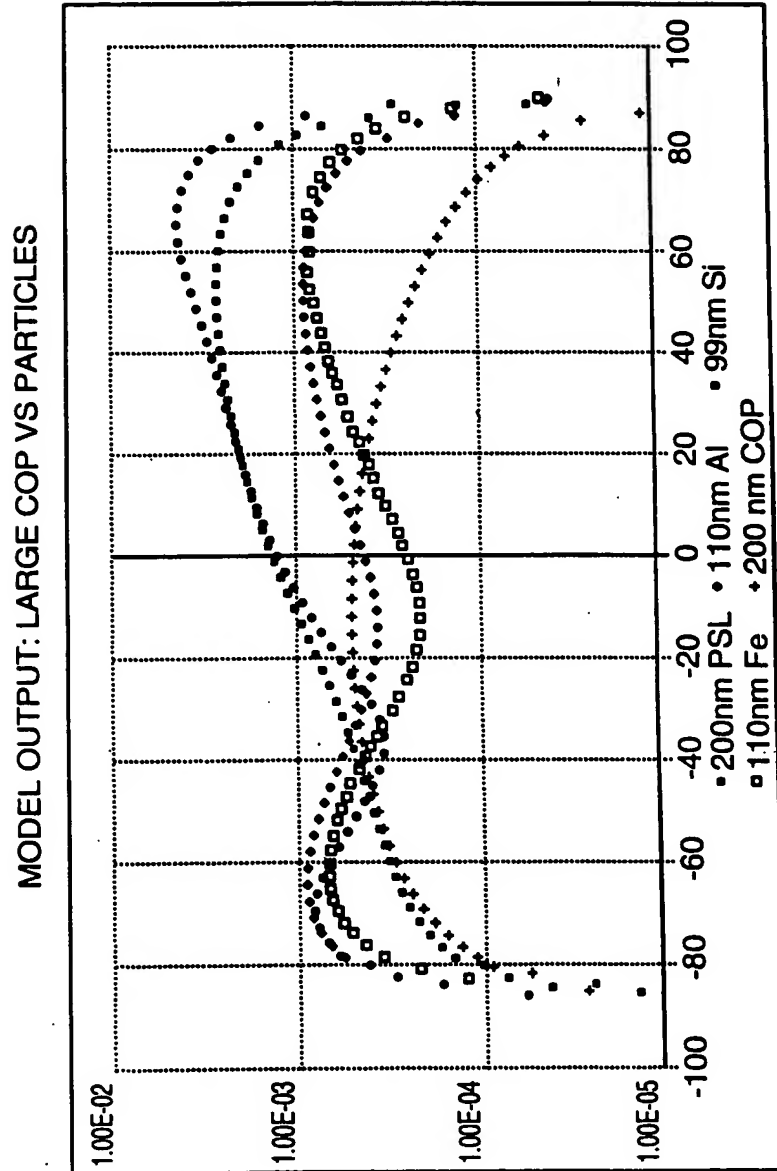


FIG. 15

COP ALGORITHM

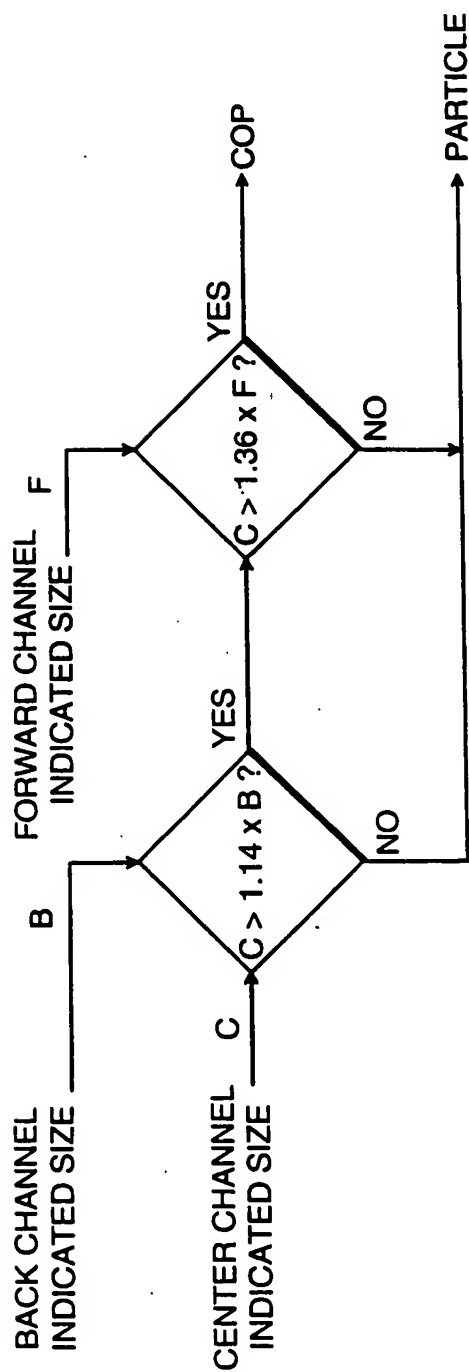


FIG. 16

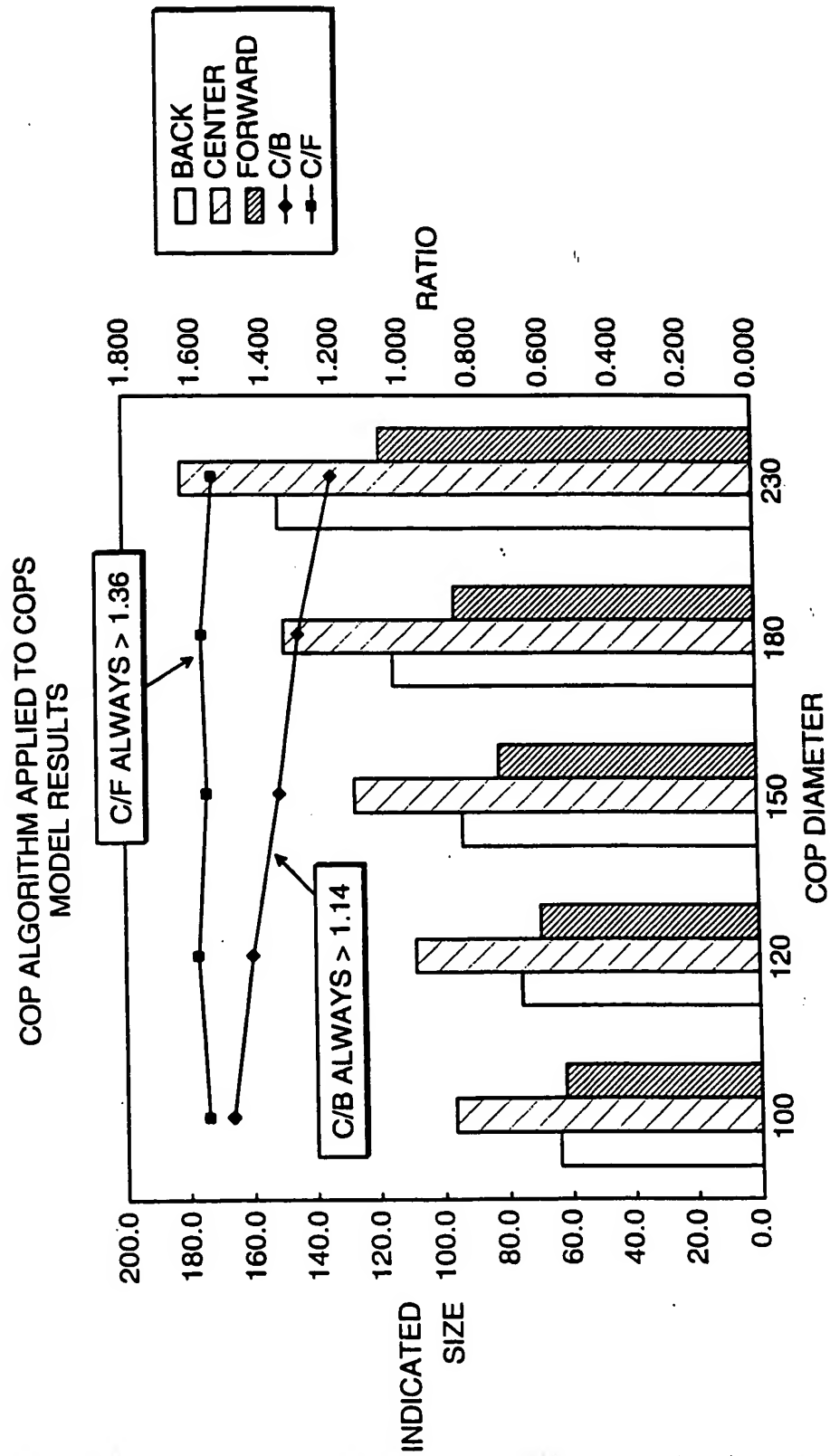


FIG. 17

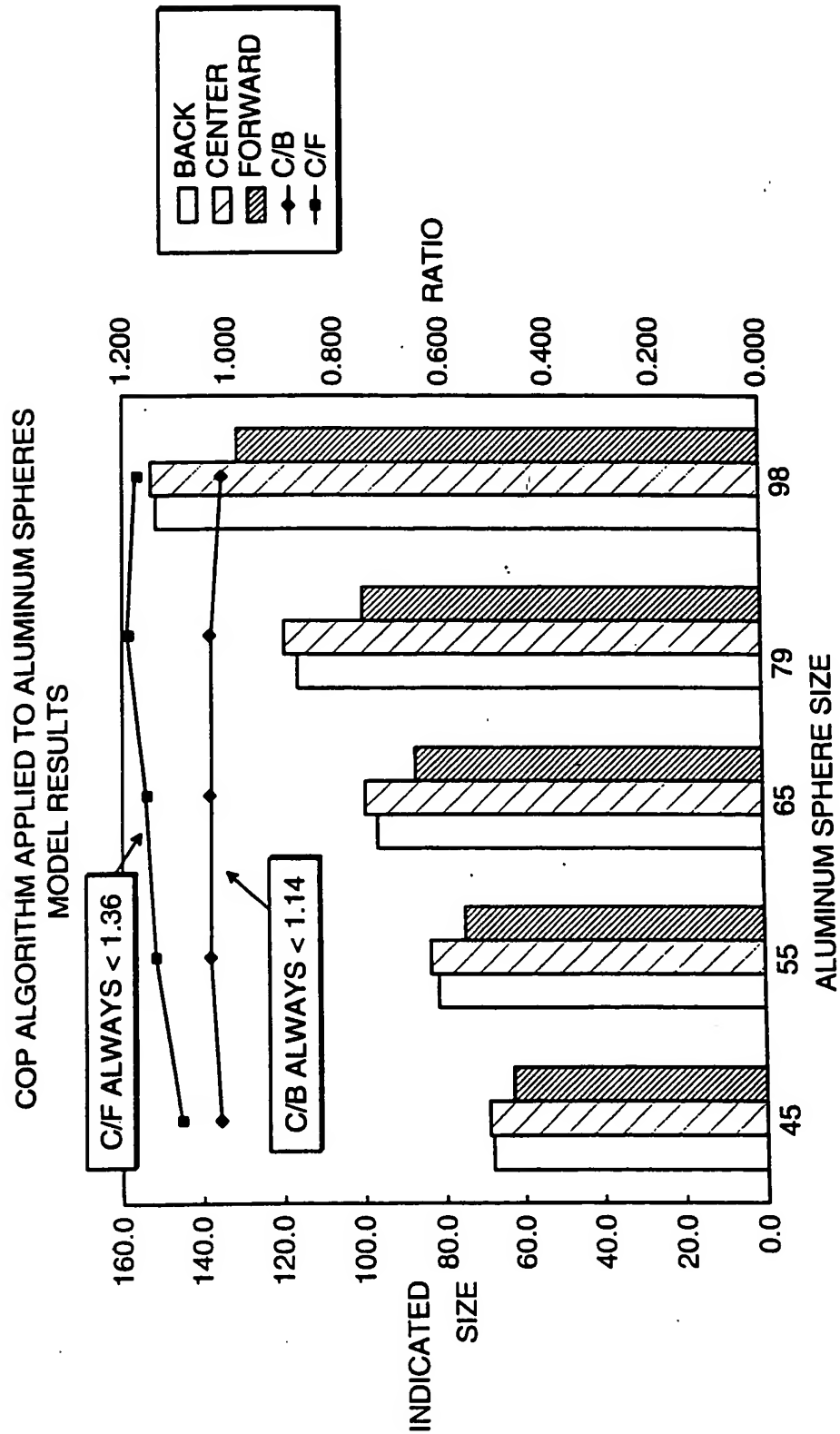


FIG. 18

AWIS PARTICLE MAP OF CLEAN CZ WAFER

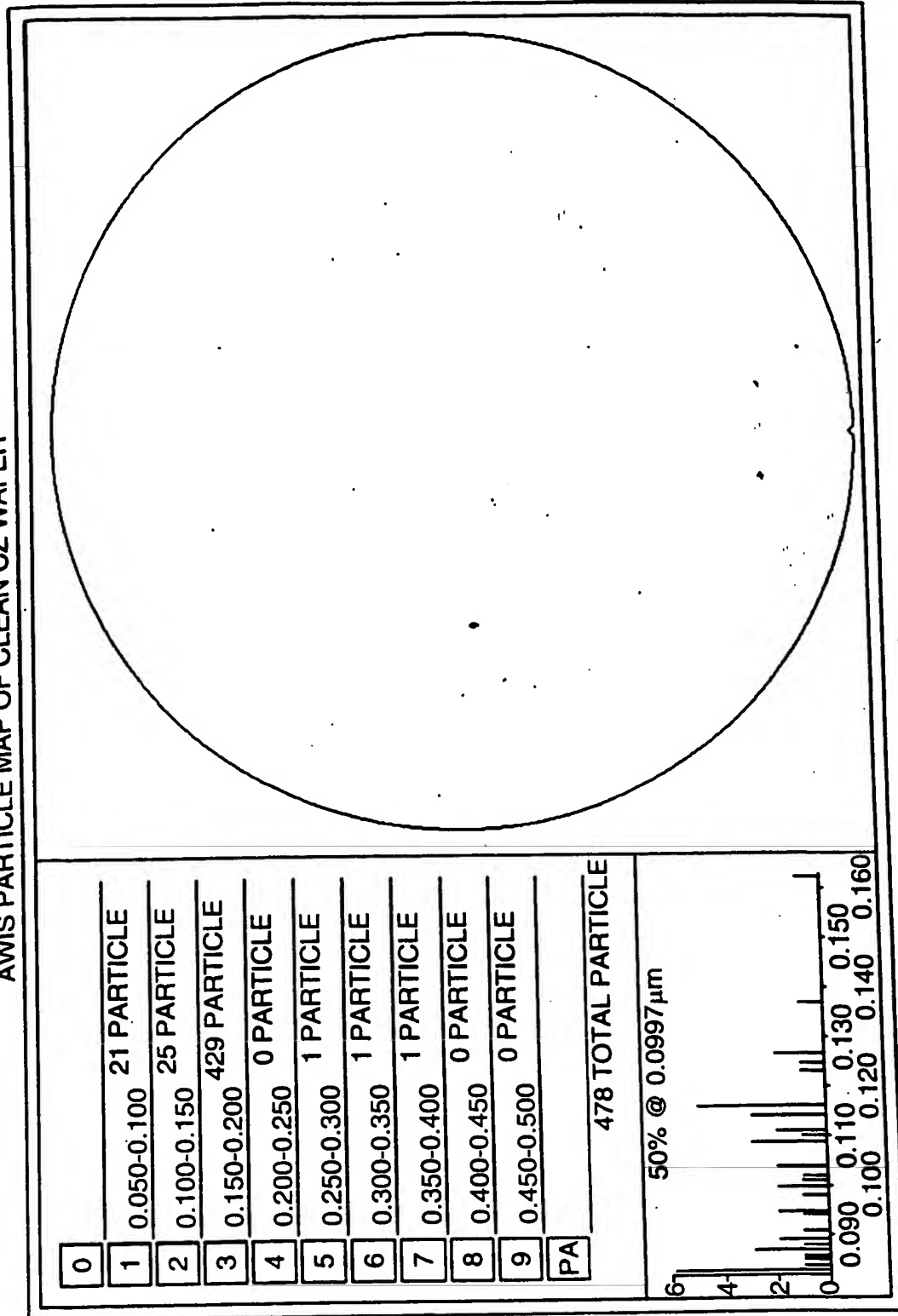


FIG. 19

AWIS COP MAP OF CLEAN CZ WAFER

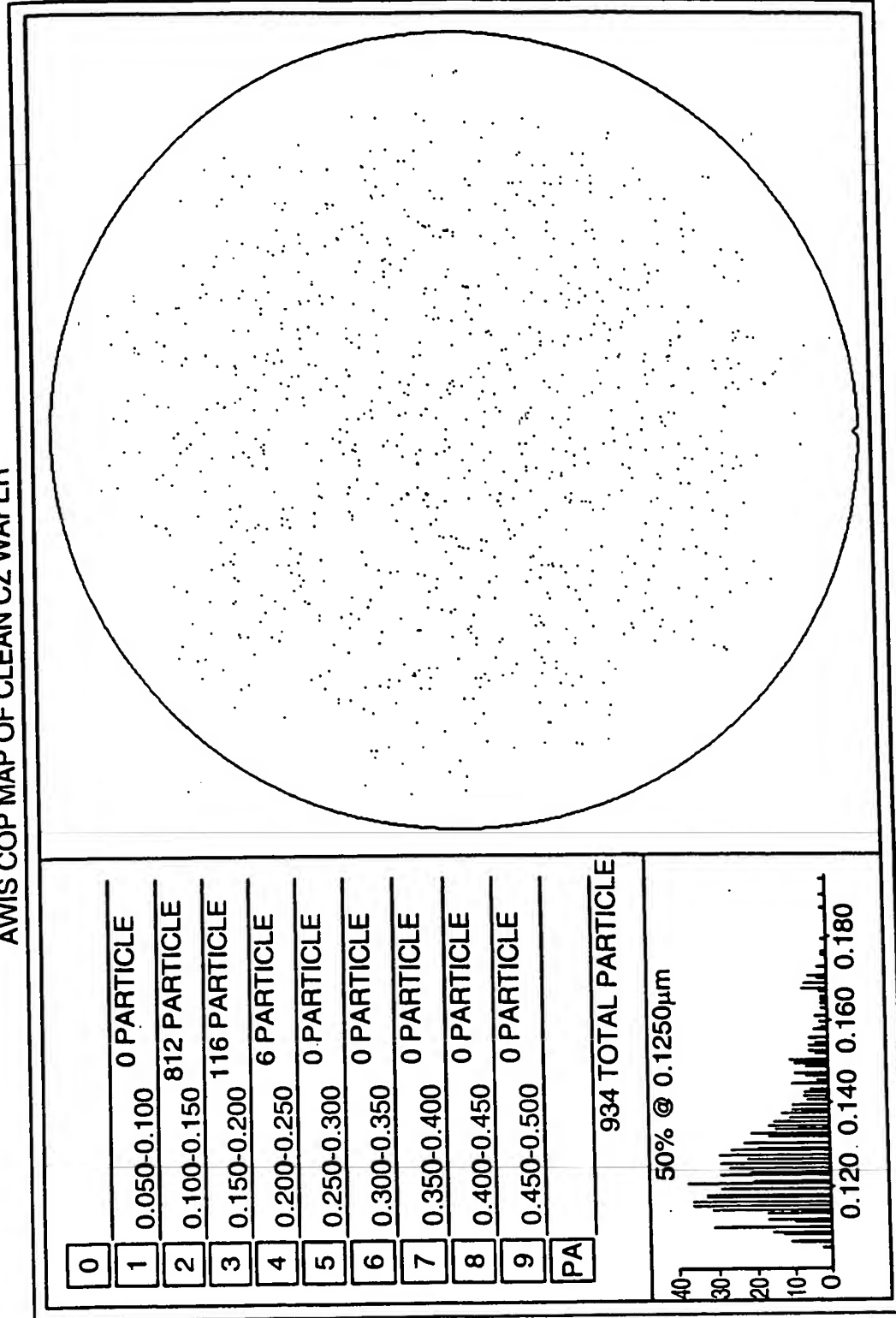


FIG. 20

AWIS PARTICLE MAP OF CZ WAFER WITH 117nm, 136nm & 157nm

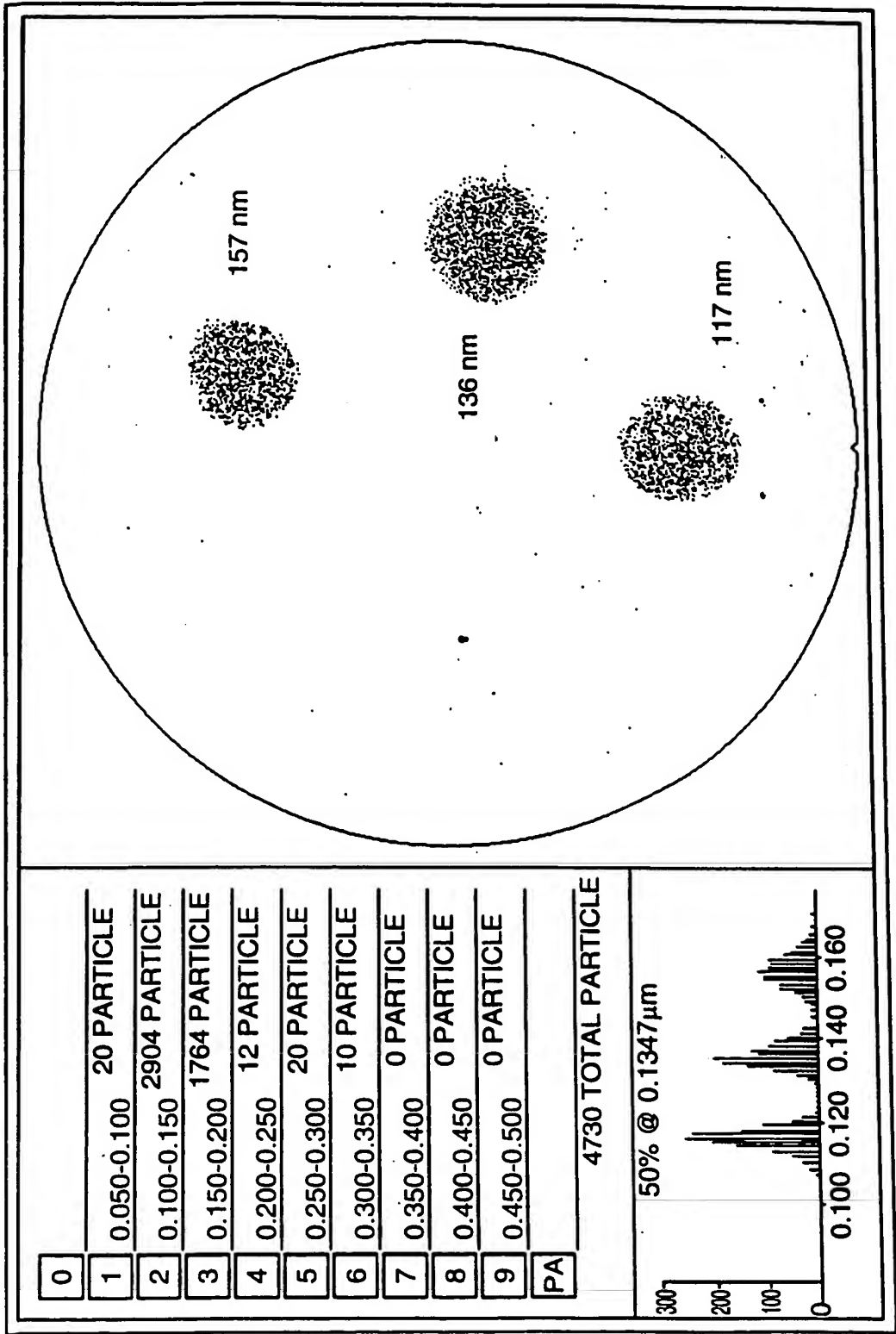


FIG. 21

AWIS COP MAP OF CZ WAFER WITH 117nm, 136nm & 157nm

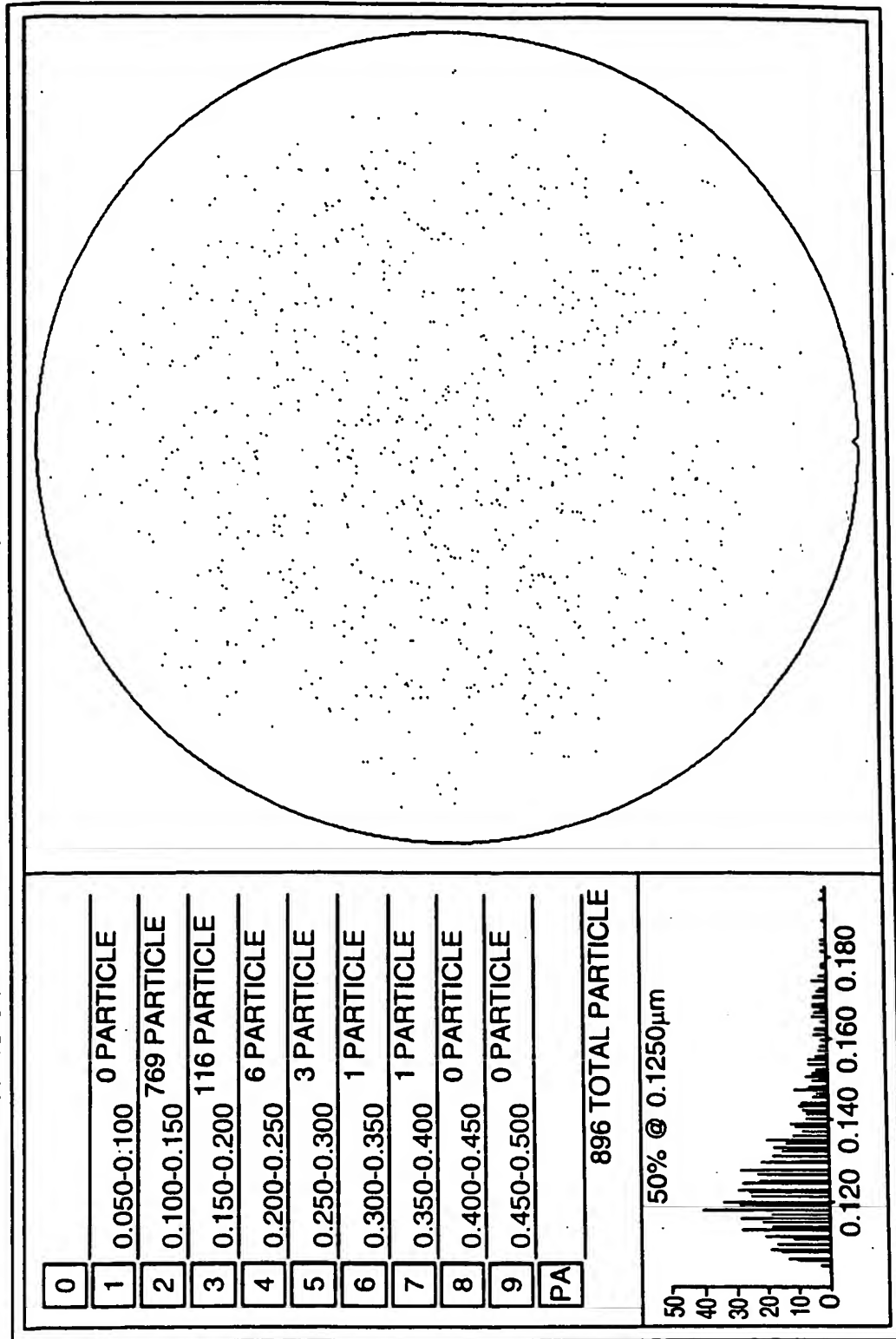


FIG. 22